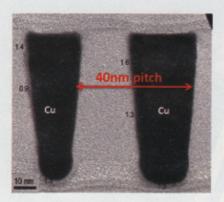
september 2010 news analysis

20nm half pitch interconnects

lmec has taken a major step towards 20nm hall pitch interconnects by producing electrically functional copper lines embedded into silicon oxide using a spacer-defined double patterning approach.

"We are very proud to be the world's first in developing and processing such small on-pitch working interconnects," said Zsolt Tokei, Programme Director of Interconnects at Imec. "Spacer-defined double patterning has recently gained interest as the patterning technique for future FLASH memory devices. I'm confident that memory companies will benefit from this state-ofthe-ert result."

Scaling of interconnects towards 20nm half pitch faces many challenges. Double patterning Ithography is needed since the metal lines cannot be achieved in a single print. Therefore, a solution is needed for the actual design split of the structures and the alignment of the different



Cross sectional TEM analysis of 20nm half pitch interconnects after integration into single damascene using a spacer defined double patterning approach

Pre-compliance EMC test services

From its dedicated engineering facility in Liverpool, MPE Ltd has for over 70 years specialised in the design and manufacture of EMC filter and capacitor solutions for a variety of applications, including vehicles, ships, power supplies, radar, computing, and communications facilities.

Now, in response to customers' requests, the company is launching pre-compliance EMC testing for the military vehicle market, providing it either on-site or in-house.

MPE is delivering a diagnostic pre-

compliance EMC test service to help define the most cost-effective chaice of EMI suppression to meet military EMC standards such as DEF STAN 59-411 and MILSTD 461, before major compliance costs are incurred. Operating a new, portable, Rohde & Schwarz model ESL6 EMI test receiver with very high precision from 9 kHz to 6 GHz frequency, MPE's evaluation service includes baseline noise measurements, comparison to specifications and identification of local areas and causes of non-compliance.



epd 7

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IRF6718	7.1 x 9.1	0.5	270
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Competitor 2	5.1 x 6.1	0.95	60
Competitor 3	5.1 x 6.1	1.5	65

* Based on data complied September 2009

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